

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|---|---|------------------|---------|------------------|
| L1 | 10665 | ((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:50 |
| L2 | 0 | ((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint near3 head | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:50 |
| L3 | 56 | ((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and print near3 head | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:52 |
| L4 | 5 | 3 and templat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:51 |
| L5 | 19 | ((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint near9 templat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:53 |
| L6 | 216017 | ((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint nand templat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:53 |
| L7 | 24 | ((((detect\$3 or measur\$3) or monitor\$3) near9 (film near5 substrate)) and imprint and templat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 11:58 |
| L8 | 24 | radiat\$3 near source and imprint near2 ((device or unit) or head) near6 templat\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:01 |
| L9 | 33 | radiat\$3 near source and imprint near2 ((device or unit) or head) and film near6 substrate | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:09 |
| L10 | 9 | radiat\$3 near source and plurality near2 ((regions or patterns) near6 (film near4 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:14 |

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| L11 | 11120 | (detect\$3 or measur\$3) near15 (film near4 substrate) plurality near2 ((regions or patterns) near6 (film near4 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:15 |
| L12 | 56 | (detect\$3 or measur\$3) near15 (film near4 substrate) and plurality near2 ((regions or patterns) near6 (film near4 substrate)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:15 |
| L13 | 136 | (detect\$3 or measur\$3) near15 (film near4 substrate) and plurality near2 ((regions or patterns) near6 film) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:16 |
| L14 | 40 | 13 and defect | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:21 |
| L15 | 0 | 14 and align\$3 near3 error | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:16 |
| L16 | 0 | 13 and align\$3 near3 error | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:16 |
| L17 | 53 | 13 and align\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:16 |
| L18 | 19 | 14 and align\$3 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:16 |
| L19 | 19 | 14 and error | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:17 |
| L20 | 13 | 18 and 19 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:17 |

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| L21 | 4 | 13 and measur\$3 near9 defect | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:23 |
| L22 | 1 | 13 and compar\$3 near9 defect | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:26 |
| L23 | 3 | 13 and ((compar\$3 or calculat\$3) or determin\$3) near6 defect | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:27 |
| L24 | 56 | 13 and ((compar\$3 or calculat\$3) or determin\$3) and (defect or error) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:36 |
| L25 | 2 | substrate near defect and templat\$3 near defect | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:28 |
| L26 | 1086 | 356/237.1 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:37 |
| L27 | 0 | 13 and 26 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:37 |
| L28 | 855 | "356"/\$.ccls. and 26 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:37 |
| L29 | 10 | "356"/\$.ccls. and 13 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/07/03 12:37 |

AT-NO: JP402159012A
DOCUMENT-IDENTIFIER: JP 02159012 A
TITLE: MASK SUBSTRATE
PUBN-DATE: June 19, 1990

INVENTOR-INFORMATION:
NAME
ARIGA, TAKASHI

ASSIGNEE-INFORMATION:
NAME FUJITSU LTD COUNTRY
N/A

APPL-NO: JP63314279
APPL-DATE: December 12, 1988

INT-CL (IPC): H01L021/027, G03F001/08
US-CL-CURRENT: 257/797

ABSTRACT:

PURPOSE: To detect any defect of a finner reticle by forming a plurality of light shielding films on a plurality of regions on a surface of a transparent substrate as a mask substrate for use in checking the reticle.

CONSTITUTION: A mask substrate 1 includes a Cr light shielding film 1b, an Al light shielding film 1c, and a Cu light shielding film 1d formed by deposition with a plurality of metals on a plurality of regions of a surface of a transparent substrate 1a. In a surface inspection device, any defect is detected by comparing shielding film patterns formed on the mask substrate 1 surface. The shielding film pattern in this case is formed of a normal reticle pattern 2a and a defective reticle pattern 2b of a reticle 2. In

case of a pin
hole as illustrated in the drawings, a pin hole through the Al
shielding film
1c is great 0.3 μ m or more in its diameter than a pin hole in the
Cr
shielding film 1b, so that any pin hole not found in the Cr shielding
film 1b
can be found in the Al shielding film 10.

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